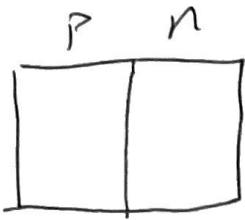
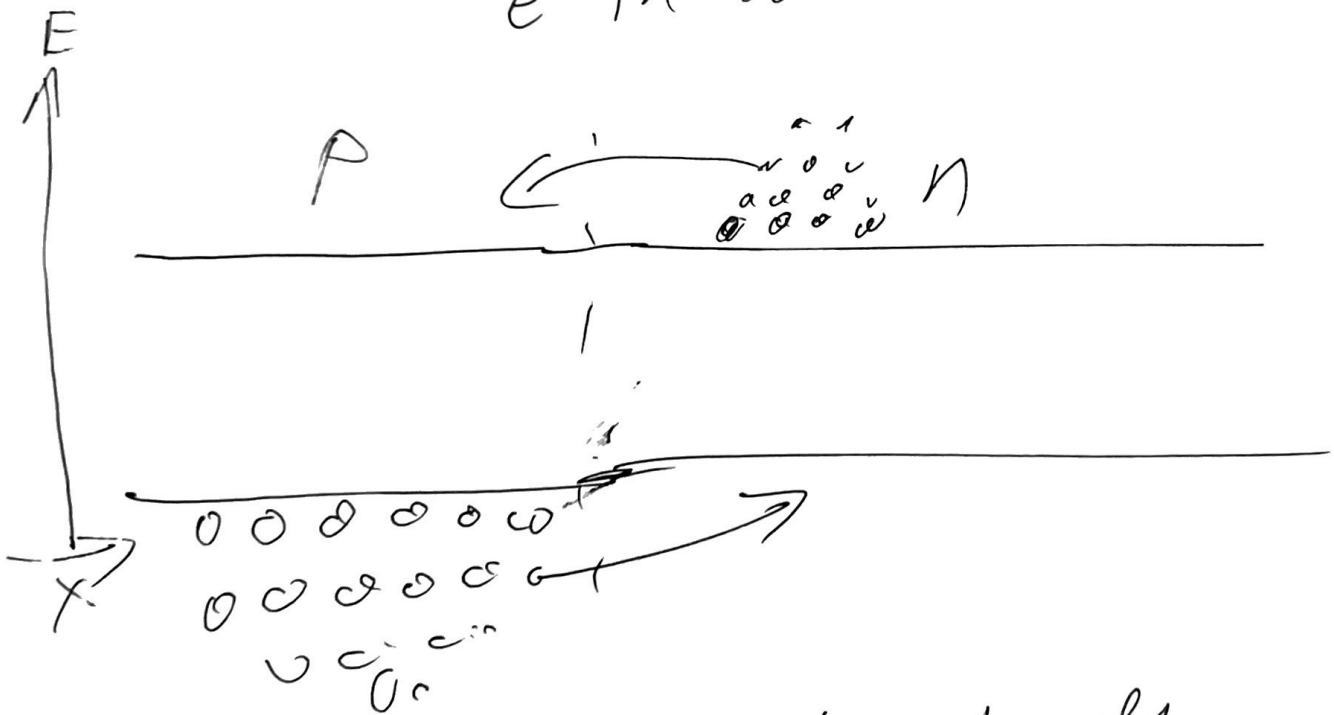


Pn



P-type semiconductor; a semicond. doped such that we have a concentration of holes in the valence band

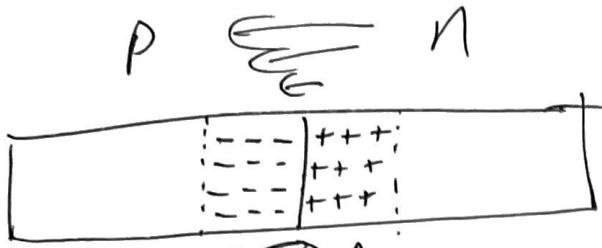
N-type semi: doped s.t. we have a concentration of e^- in conduction band



- when we put the pn junction together we get a depletion region at the interface

(2)

— N I M —

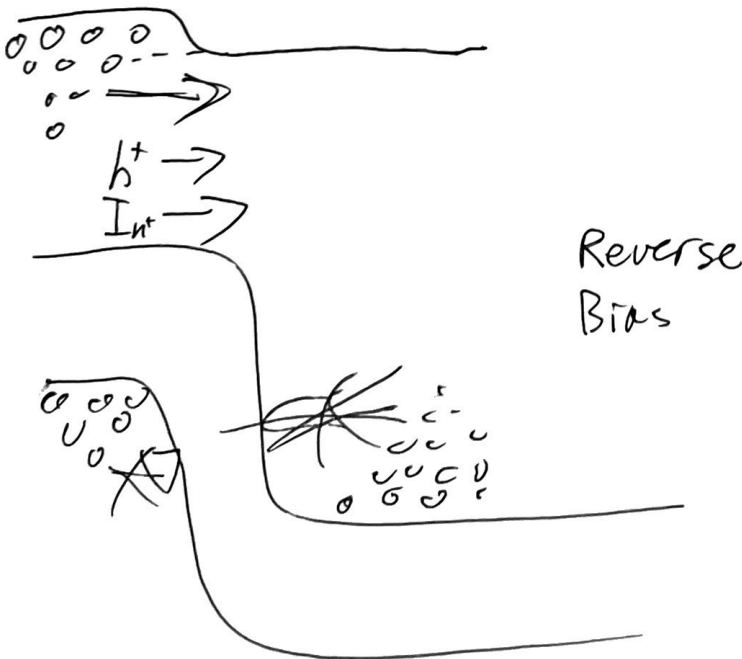


no concent.
of holes

no concentration of e^-

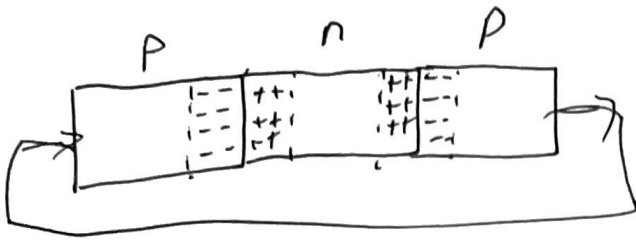


Forward
Bias

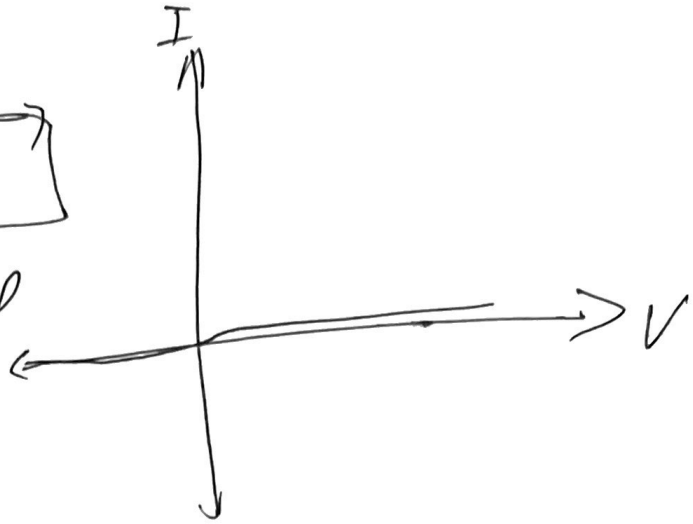


Reverse
Bias

3



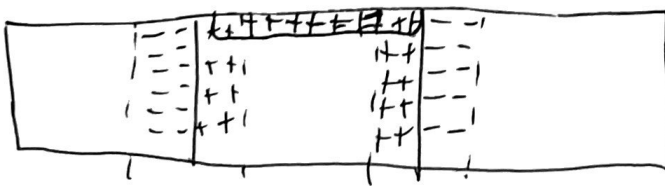
Bottom of conduction Band



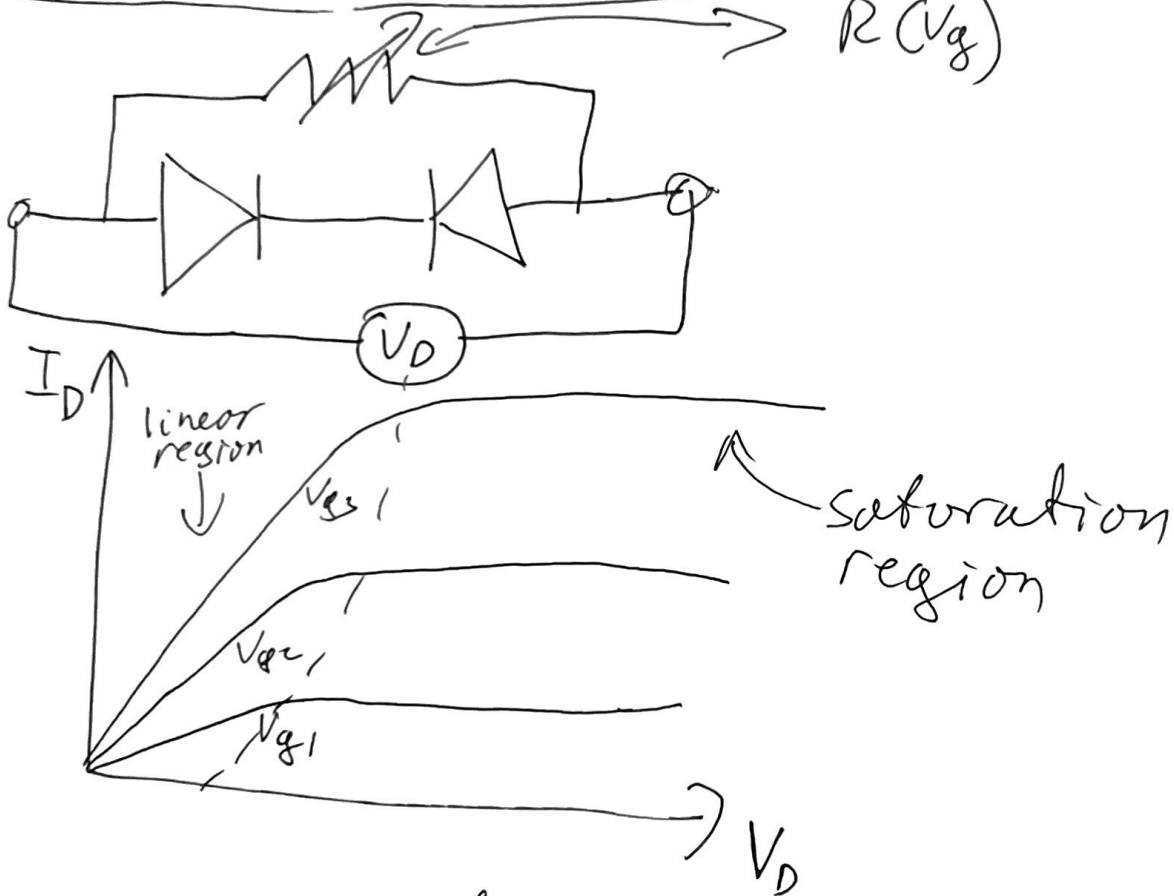
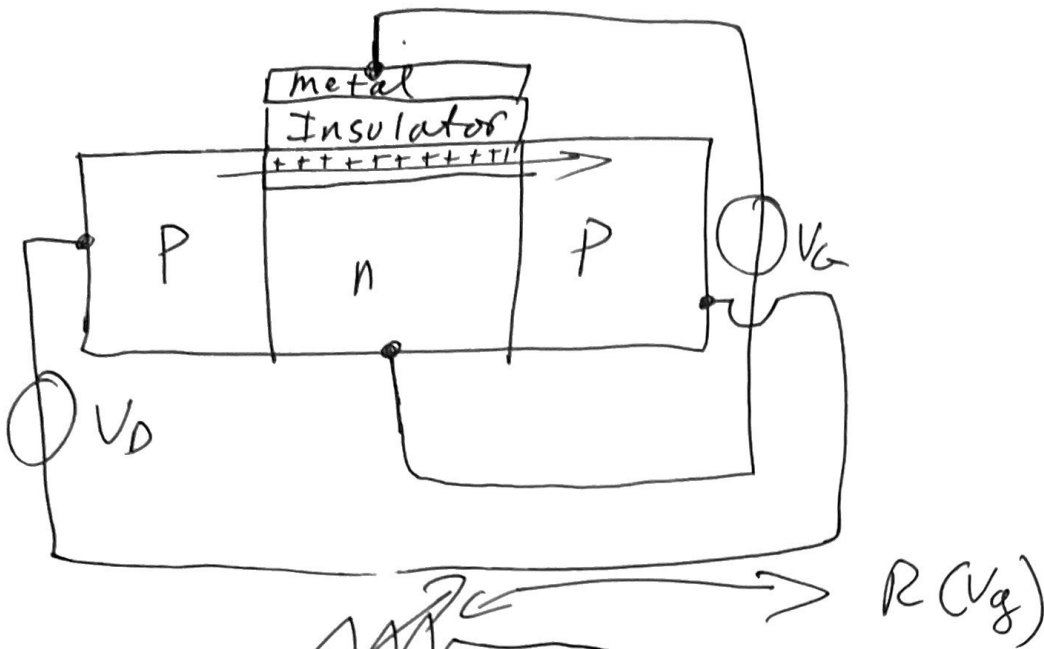
$$R = \rho \frac{l}{A}$$

$$\rho \propto \frac{1}{n e \mu}$$

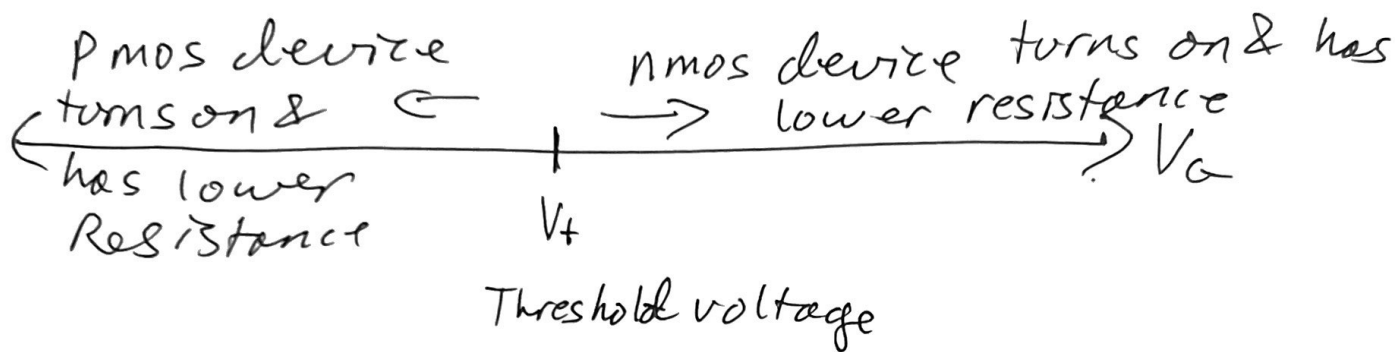
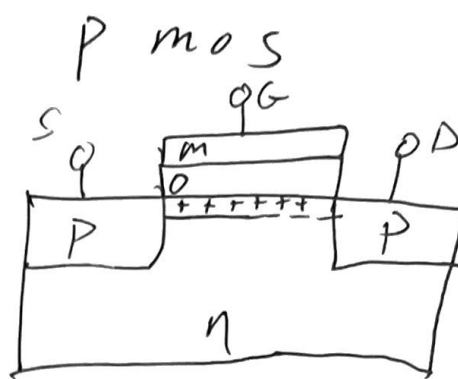
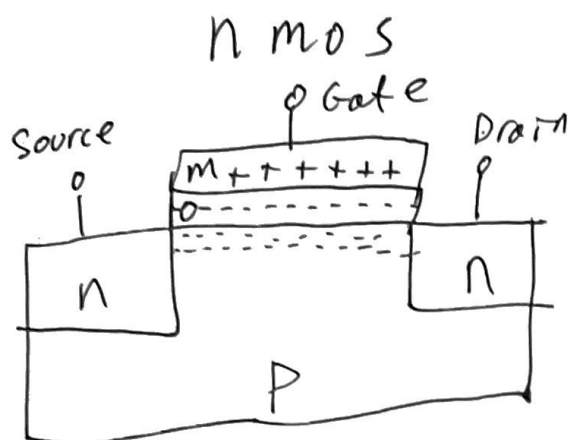
$$\rho \propto \frac{1}{\underset{\substack{\uparrow \\ \text{conc elec}}}{n} + \underset{\substack{\uparrow \\ \text{conc holes}}}{p}}$$



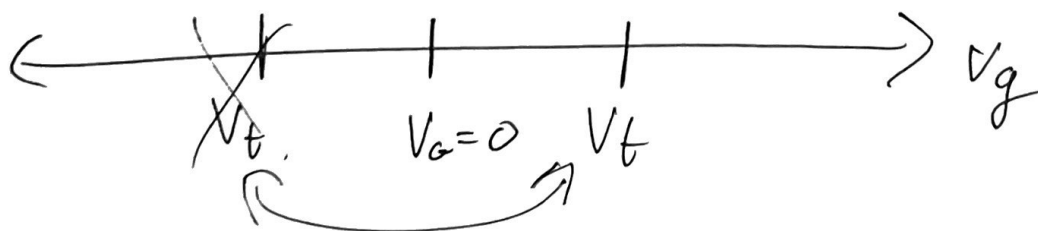
(4)



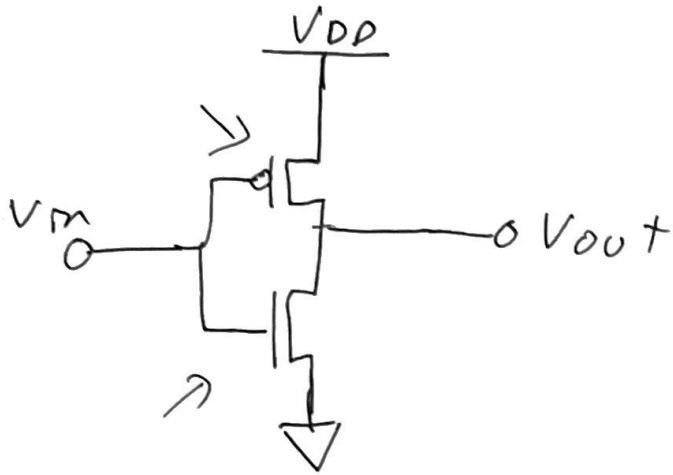
If V_G is below the threshold voltage, then you don't short out the back-to-back pn junctions



The threshold voltage, V_T , is the voltage at which the channel forms.

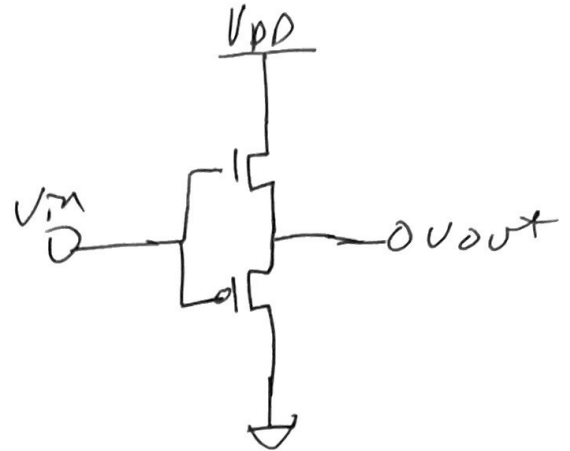


CMOS Inverter



In	out
0	1
1	0

CMOS Buffer



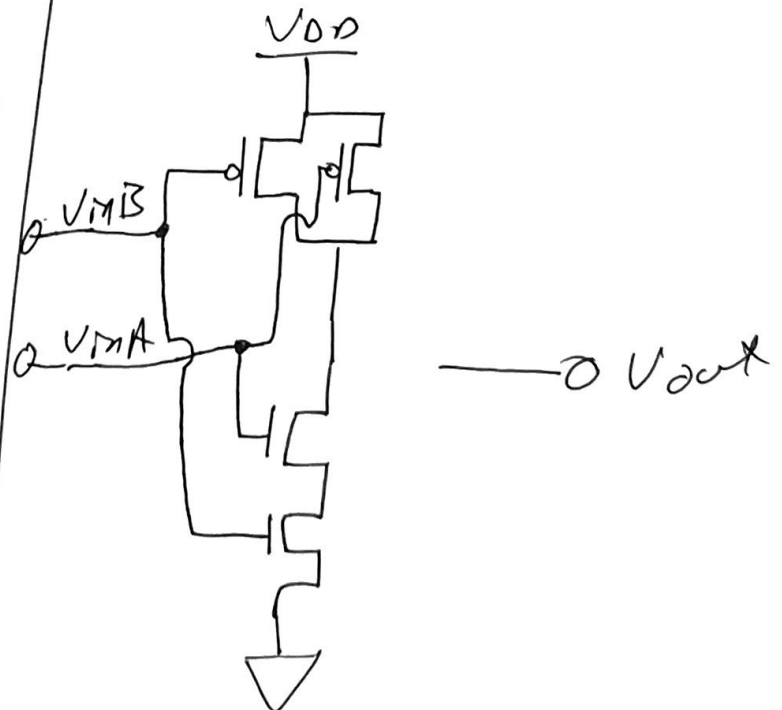
In	out
0	0
1	1

CMOS NAND Gate

A and B

A	B	out
0	0	0
0	1	0
1	0	0
1	1	1

A	B	out
0	0	1
0	1	1
1	0	1
1	1	0



~~CMOS OR Gate~~